

Amendments to the Claims

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1-2. (Canceled)

3. (Previously presented) A method for manufacturing a magnetic recording disk, comprising:

preparing magnetic-recording-layer preparation on a substrate; and

preparing an anisotropy-allowing-layer on the substrate prior to the magnetic-recording-layer preparation;

the anisotropy allowing layer allowing magnetic anisotropy to the magnetic recording layer;

the anisotropy-allowing layer being made of nitride of niobium, tantalum, niobium alloy or tantalum alloy; or nitrogen-including niobium, tantalum, niobium alloy or tantalum alloy;

the anisotropy-allowing layer being prepared by sputtering a larger number of sputtered particles having the direction component along the direction of the magnetic anisotropy incident on the substrate than sputtered particles not having direction component along the direction of the magnetic anisotropy to be allowed.

4. (Previously presented) The method for manufacturing a magnetic recording disk as claimed in claim 3, further comprising exposing the prepared anisotropy-allowing layer to atmospheric gas, nitrogen gas or oxygen gas.

5-20. (Canceled)

21. (Previously presented) The method for manufacturing a magnetic recording disk as claimed in claim 3, further comprising screening the sputtered particles not having direction component along the direction of the magnetic anisotropy to be allowed, thereby making relatively a larger number of sputtered particles having the direction component along the direction of the magnetic anisotropy to be allowed incident on the substrate, than sputtered particles not

having direction component along the direction of the magnetic anisotropy to be allowed.

22. (Previously presented) The method for manufacturing a magnetic recording disk as claimed in claim 21, wherein the screened sputtered particles are the particles traveling to the direction interconnecting the center of a target and the center of the substrate.